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(54) Title: ALKOXYDISILOXANES AND DENSE ORGANOSILICA FILMS MADE THEREFROM

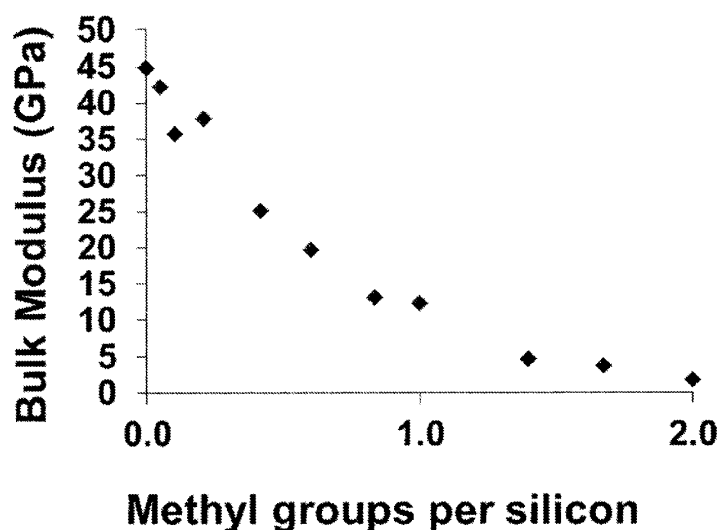


Figure 1

(57) Abstract: A method for making a dense organosilicon film with improved mechanical properties includes the steps of: providing a substrate within a reaction chamber; introducing into the reaction chamber a gaseous composition comprising alkoxydisiloxane; and applying energy to the gaseous composition comprising alkoxydisiloxane in the reaction chamber to induce reaction of the gaseous composition comprising alkoxydisiloxane to deposit an organosilicon film on the substrate, wherein the organosilicon film has a dielectric constant of from ~ 2.50 to ~ 3.30, an elastic modulus of from ~ 6 to ~ 35 GPa, and an at. % carbon of from ~ 10 to ~ 40 as measured by.

[Continued on next page]

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